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# Particle Tracking with 3D Monolithically Stacked CMOS Active Pixel Sensors

D. Passeri<sup>(1,2)</sup>, L. Servoli<sup>(2)</sup>, A. Morozzi<sup>(1,2)</sup>  
D. Magalotti<sup>(2,3)</sup>, L. Piperku<sup>(1)</sup>

(1) Dipartimento di Ingegneria - Università di Perugia, Italy

(2) Istituto Nazionale Fisica Nucleare - Sezione di Perugia, Italy

(3) Dipartimento di Ingegneria, Università di Modena, Italy

9<sup>th</sup> "Trento" Workshop on Advanced Silicon Radiation Detectors  
(3D and p-type Technologies)

26-28 February 2014, Genova - Italy

# Outline

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- ✓ Introduction: motivation and aim, background.
- ✓ The RAPS04-3D structures: (2D), 3D “not aligned”, 3D “aligned”.
- ✓ Electrical characterization (noise).
- ✓ X-ray characterization (signal).
- ✓ Characterization with 3MeV protons @ LABEC, Florence (Italy).
- ✓ The next prototype: RAPS05-3D.
- ✓ Conclusions.

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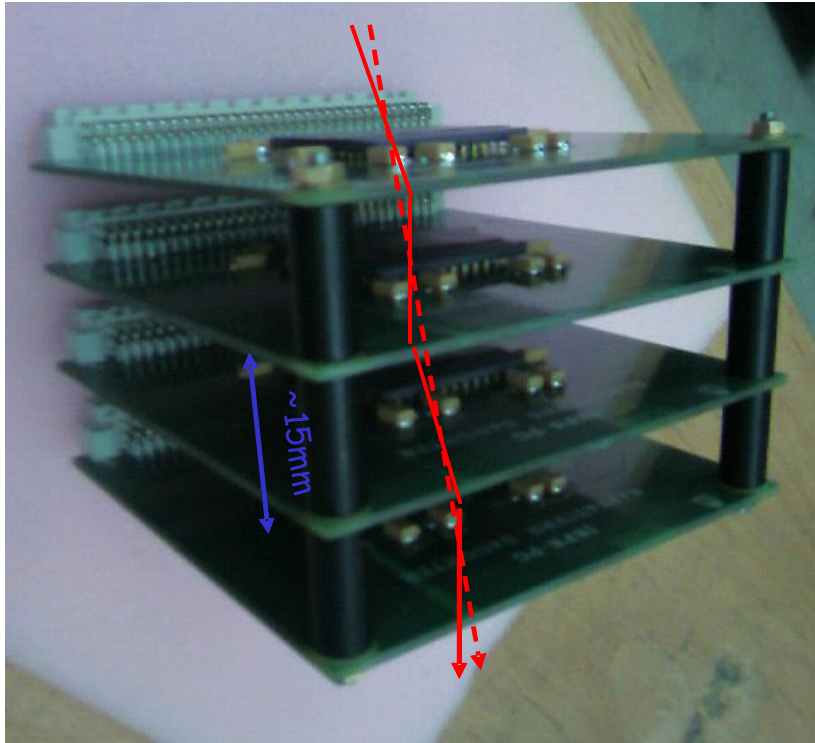
# Motivation and Aim

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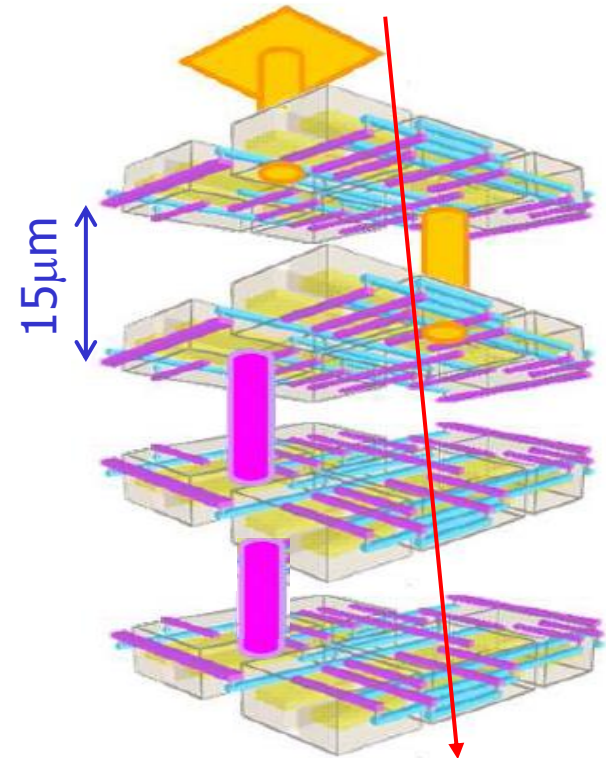
- ✓ The IC technology trend is to move from 3D flexible configurations (package on package, stacked dies) to 3D ICs:
  - increased electrical performances;
  - cost of 3D integration may be cheaper than to keep shrinking 2D.
- ✓ Perspective advantages for particle tracking / vertex detectors:
  - separation of sensor, analog read-out electronics, A/D conversion layers (increased fill-factor, performance).
- ✓ All-in-one chip featuring multiple, stacked, fully functional CMOS APS detector layers:
  - momentum measurement (impact point and trajectory) with a single detector;
  - low material detector (reduced multiple scattering issues).

# Basic principle

- ✓ 3D monolithically-stacked CMOS Active Pixel Sensor detector for single ionizing particle trajectory and momentum identification.



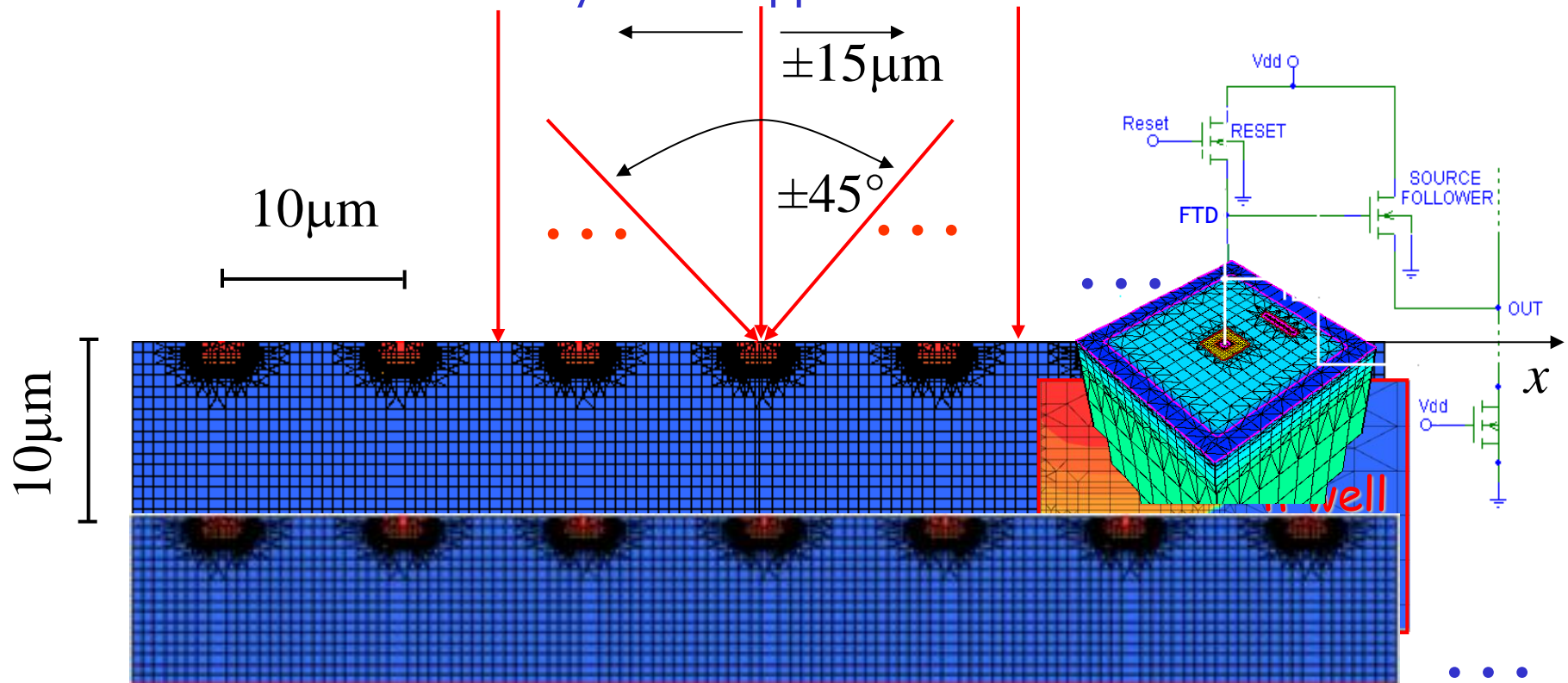
Stack of separate multi-layer CMOS APS detectors.  
Worries: multiple scattering and material budget...



Stack of monolithically integrated (vertical scale or 3D) CMOS APS detectors.

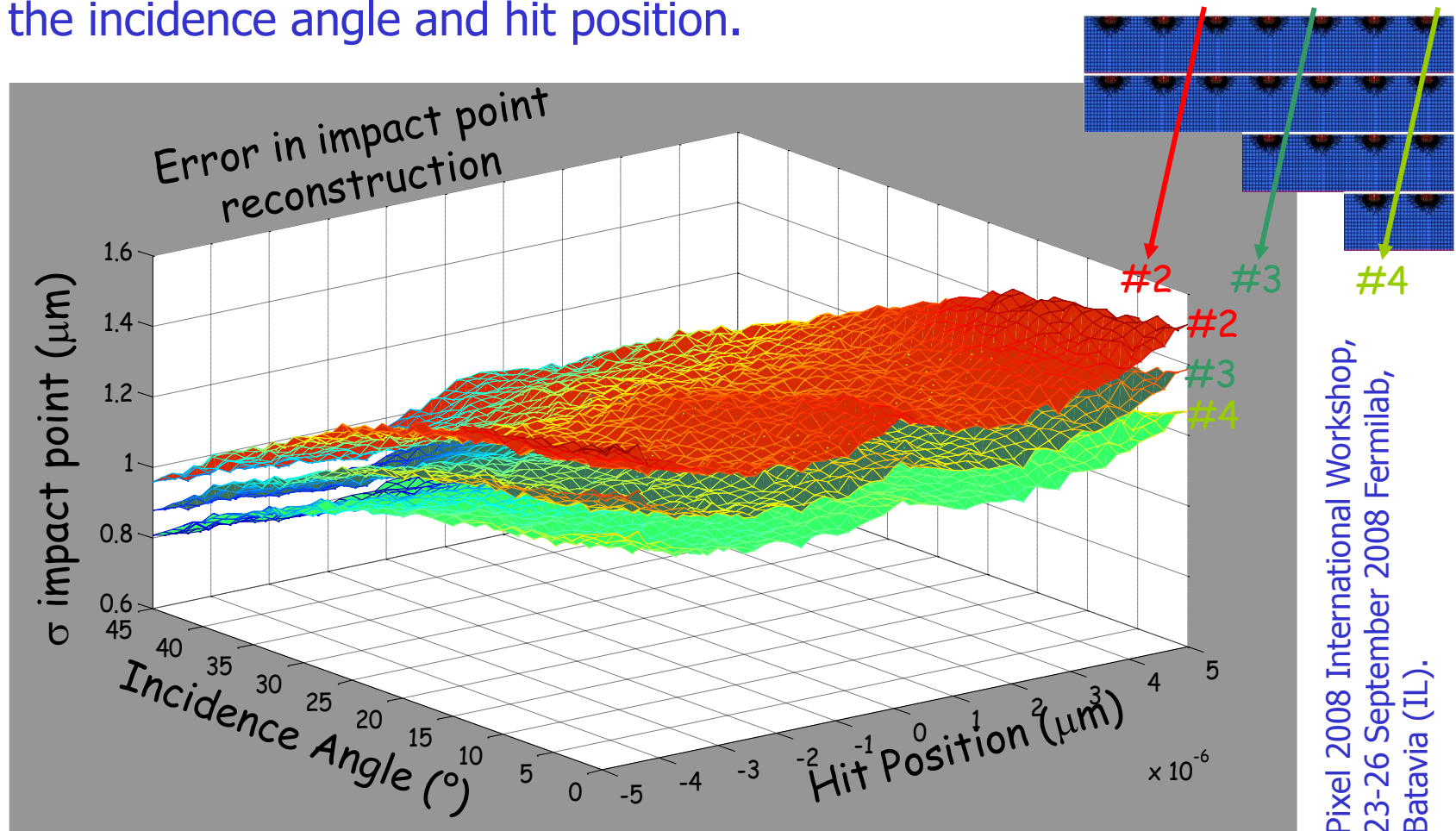
# 3D Monolithically Stacked CMOS APS

- ✓ Is it possible to gain information (on particle trajectory and momentum) from small pixels / small inter-layer distances?
- ✓ Device/Circuit simulations of a CMOS Active Pixel Sensor to assess the suitability of the approach.



# Impact point reconstruction error

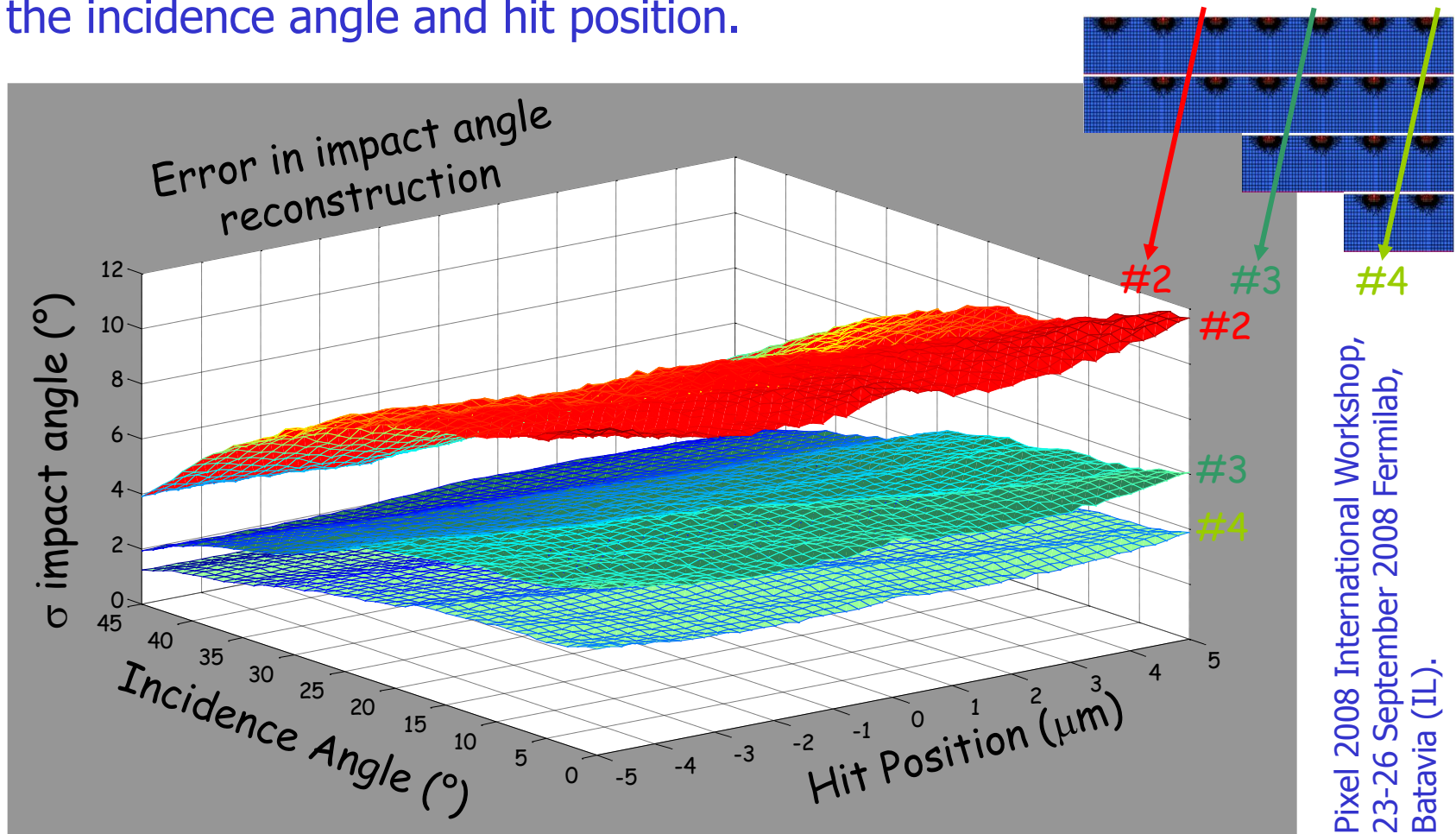
- ✓ Standard deviation of the impact point calculation as a function of the incidence angle and hit position.



Pixel 2008 International Workshop,  
23-26 September 2008 Fermilab,  
Batavia (IL).

# Incidence angle reconstruction error

- ✓ Standard deviation of the incidence angle calculation as a function of the incidence angle and hit position.



Pixel 2008 International Workshop,  
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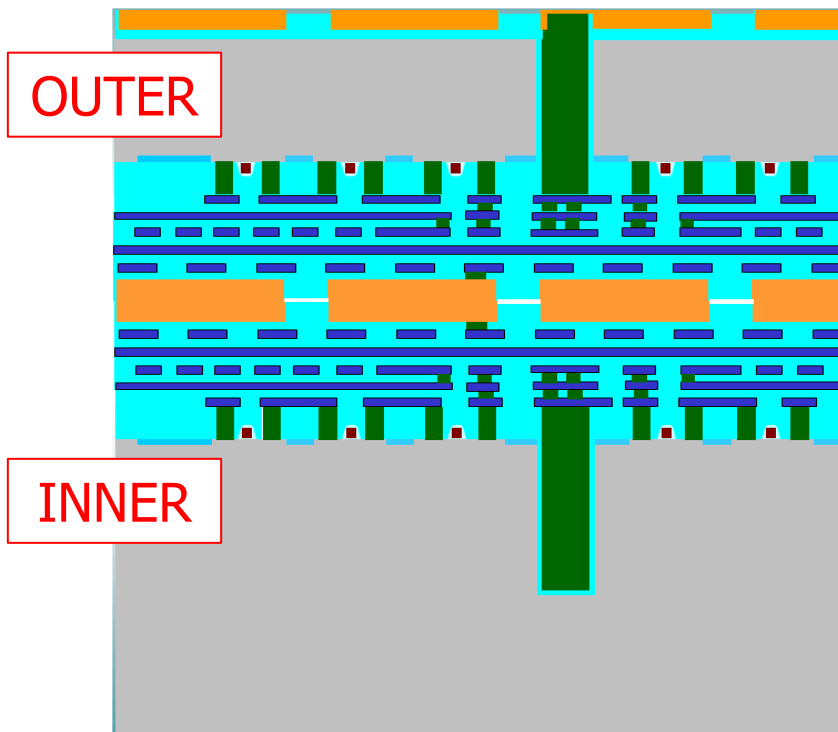
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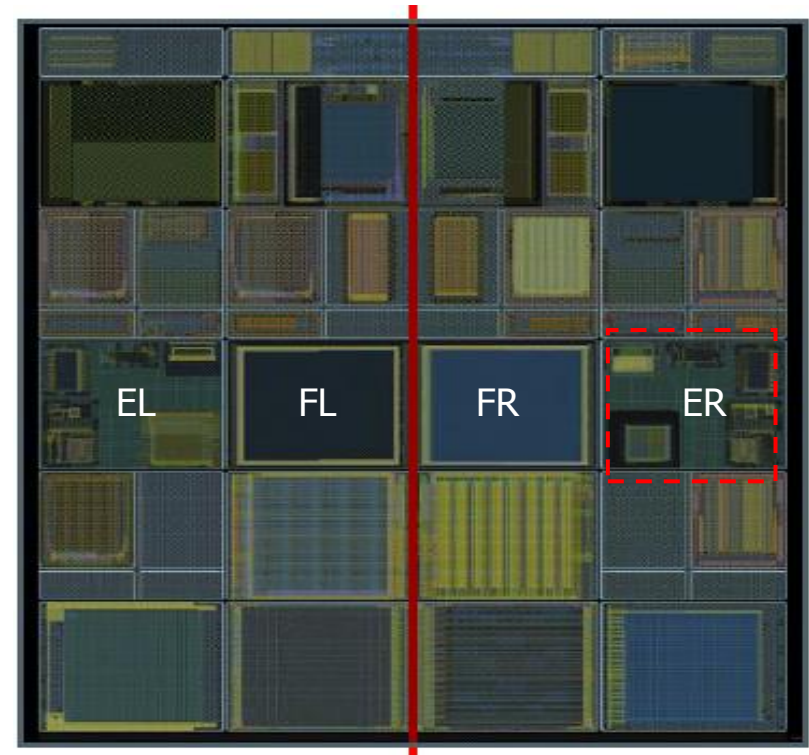
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# The 3D Tezzaron 130nm Technology

- ✓ 3D-IC consortium ([3dic.fnal.gov](http://3dic.fnal.gov))  
Access to 3D Tezzaron/Chartered 130nm technology.



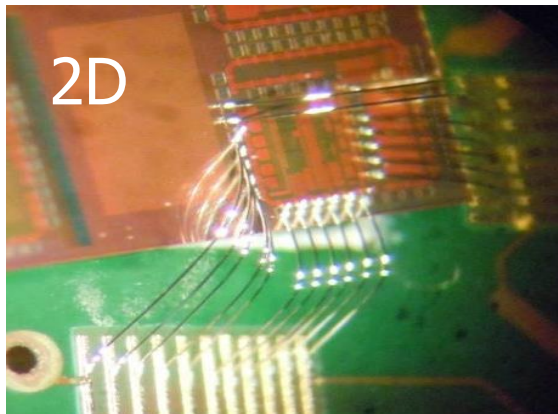
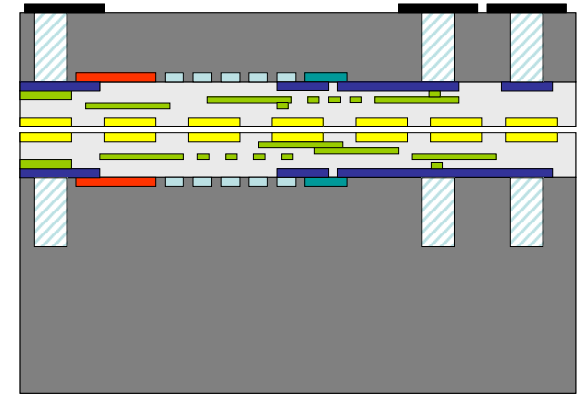
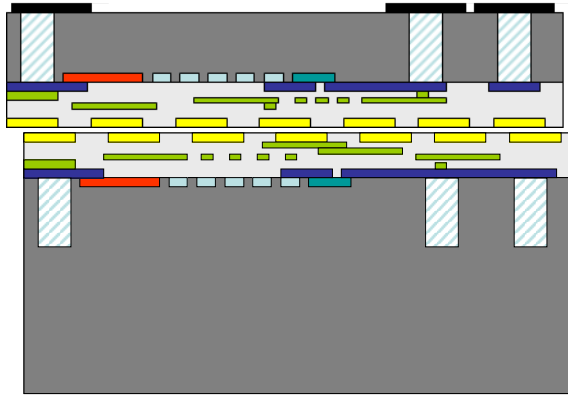
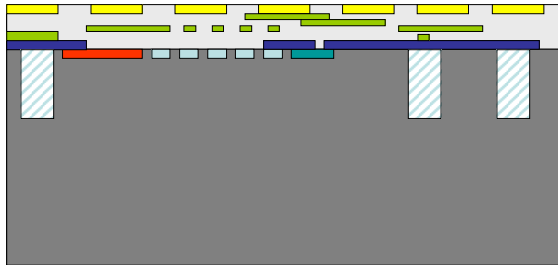
Schematic cross-section of a front-to-front chip bonding (thinned top tier)



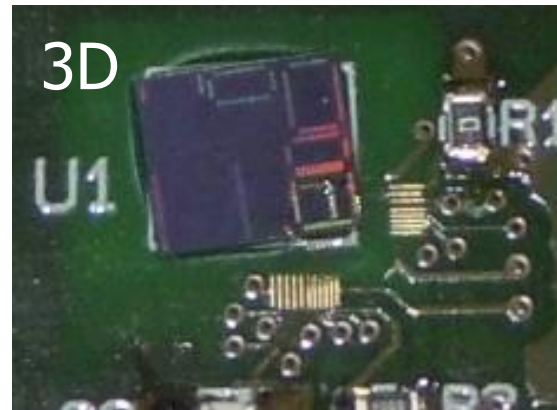
MPW run ("HEP oriented")  
VIPIX – INFN gr. V (sub-reticles E & F).

# The chip structures

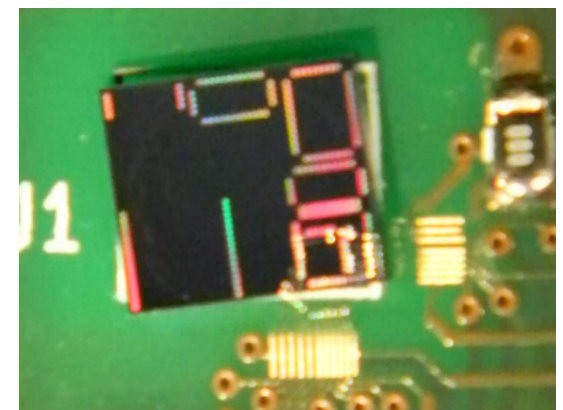
Tezzaron/GlobalFoundries  
3D-IC Integrated 2-tier stack  
130nm CMOS



2D.



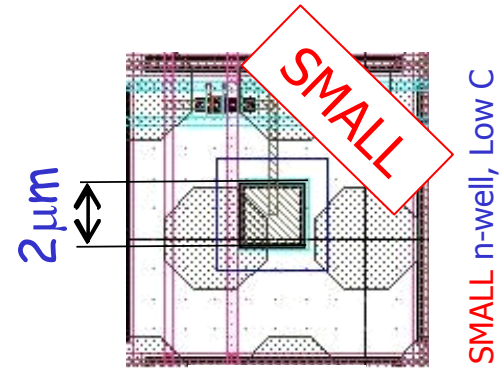
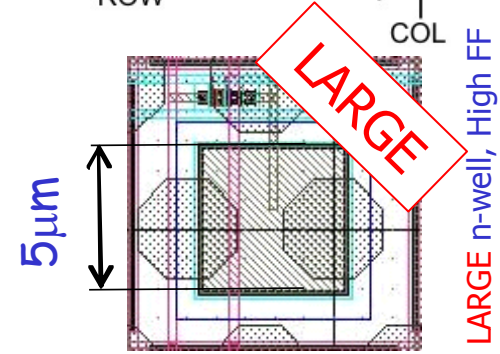
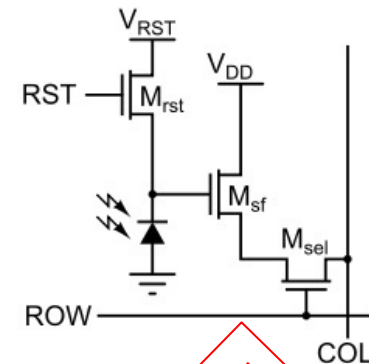
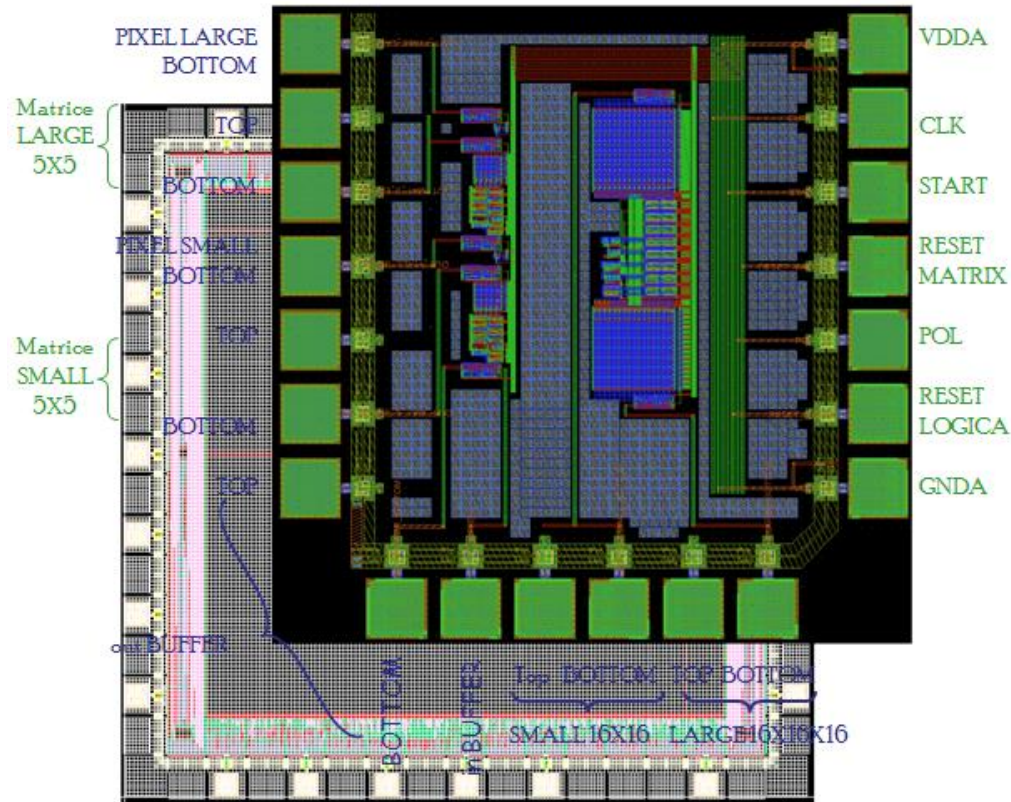
3D Not Aligned.



3D Aligned  
(Ziptronix/Tezzaron).

# The RAPS04-3D structures

- ✓ Active Pixel Sensor 3T architecture with different photodiode area.



10  $\mu\text{m}$

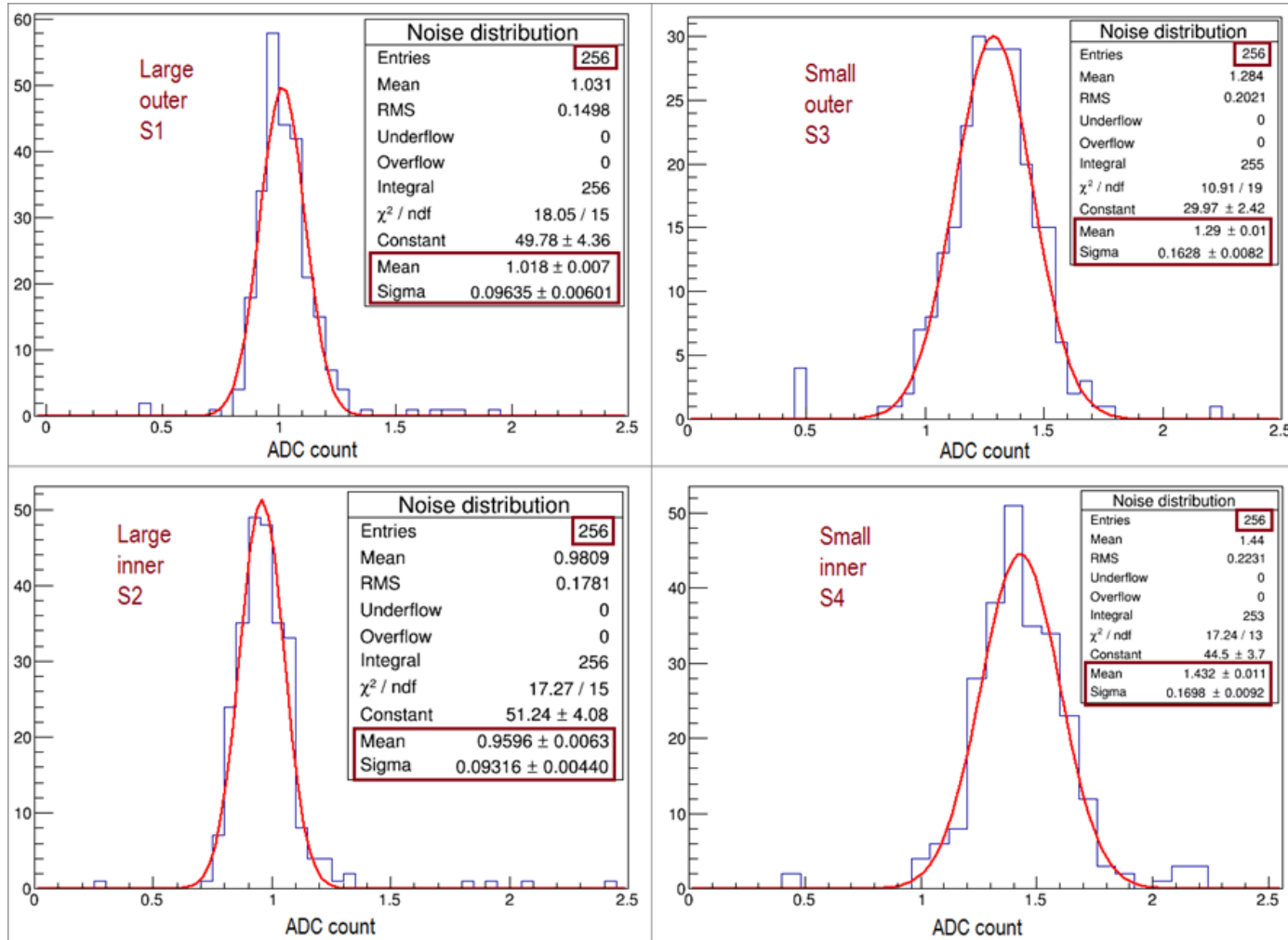
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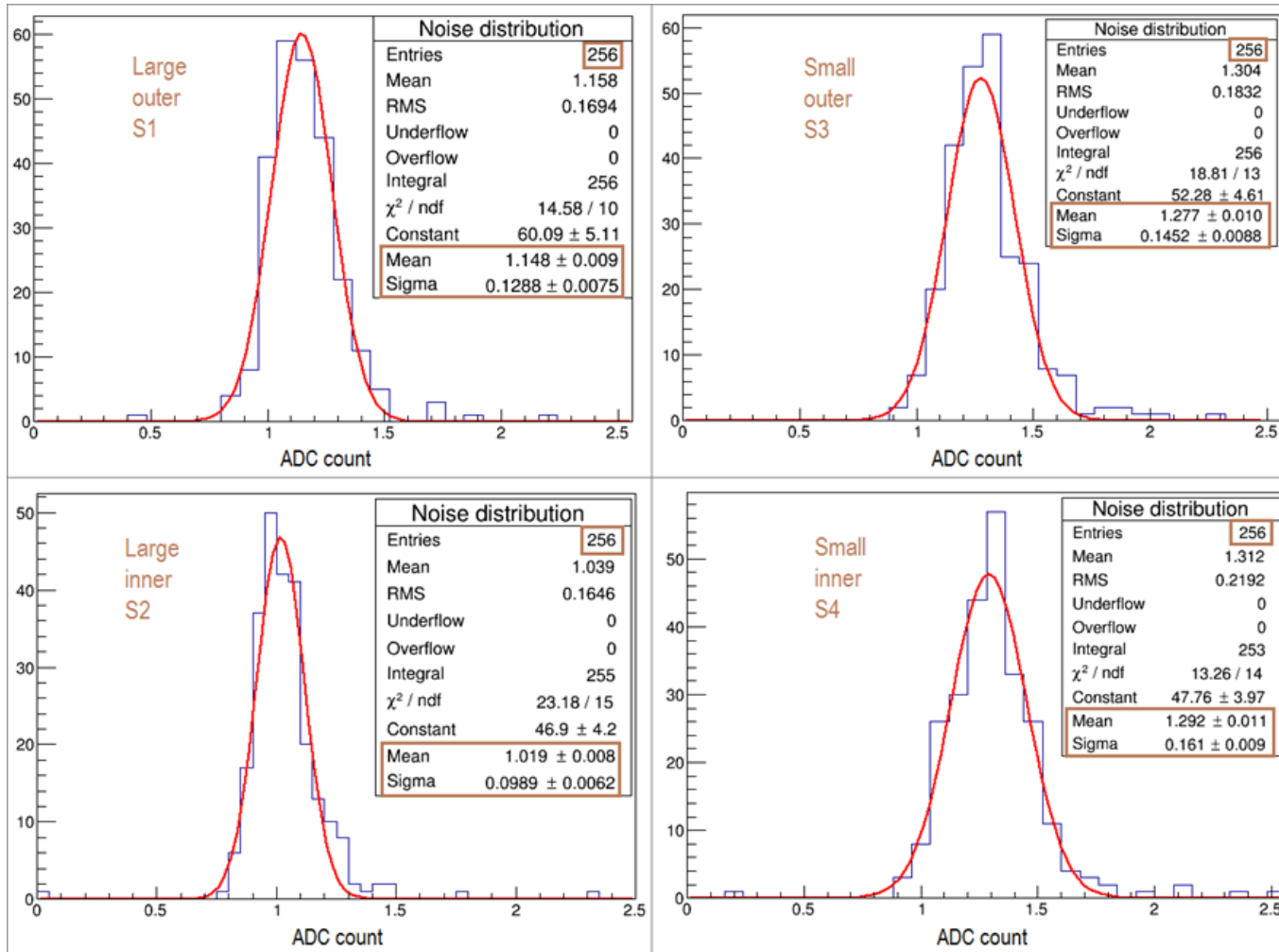
# Electrical Characterization

- ✓ Noise distribution 16x16 pixel matrices – Tezzaron bonded chip



# Electrical Characterization (2)

- ✓ Noise distribution 16x16 pixel matrices – Ziptronix bonded chip



# Outline

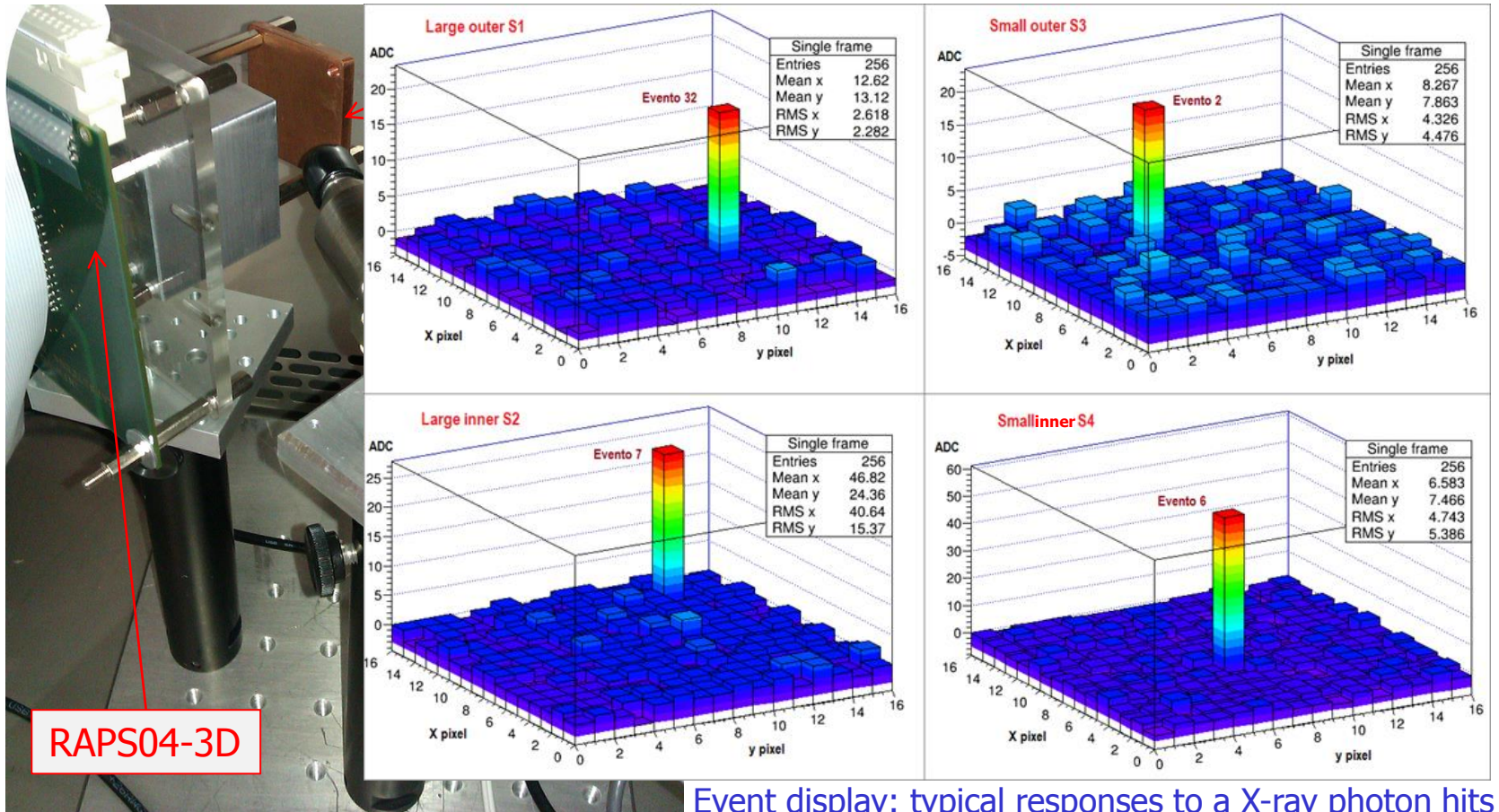
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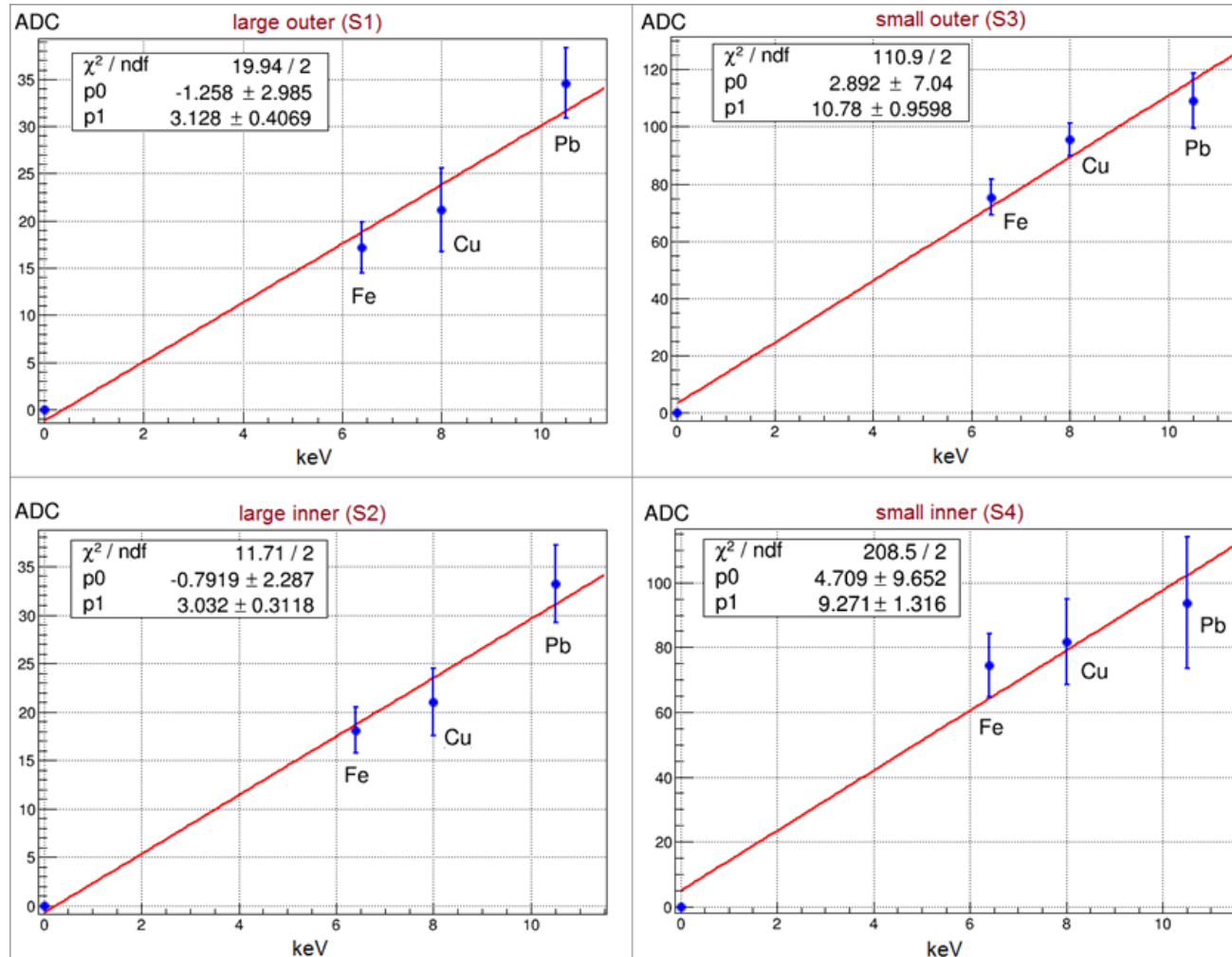
# Functional Characterization (X-rays)

- ✓ The X-ray set-up @ INFN Perugia Laboratories.



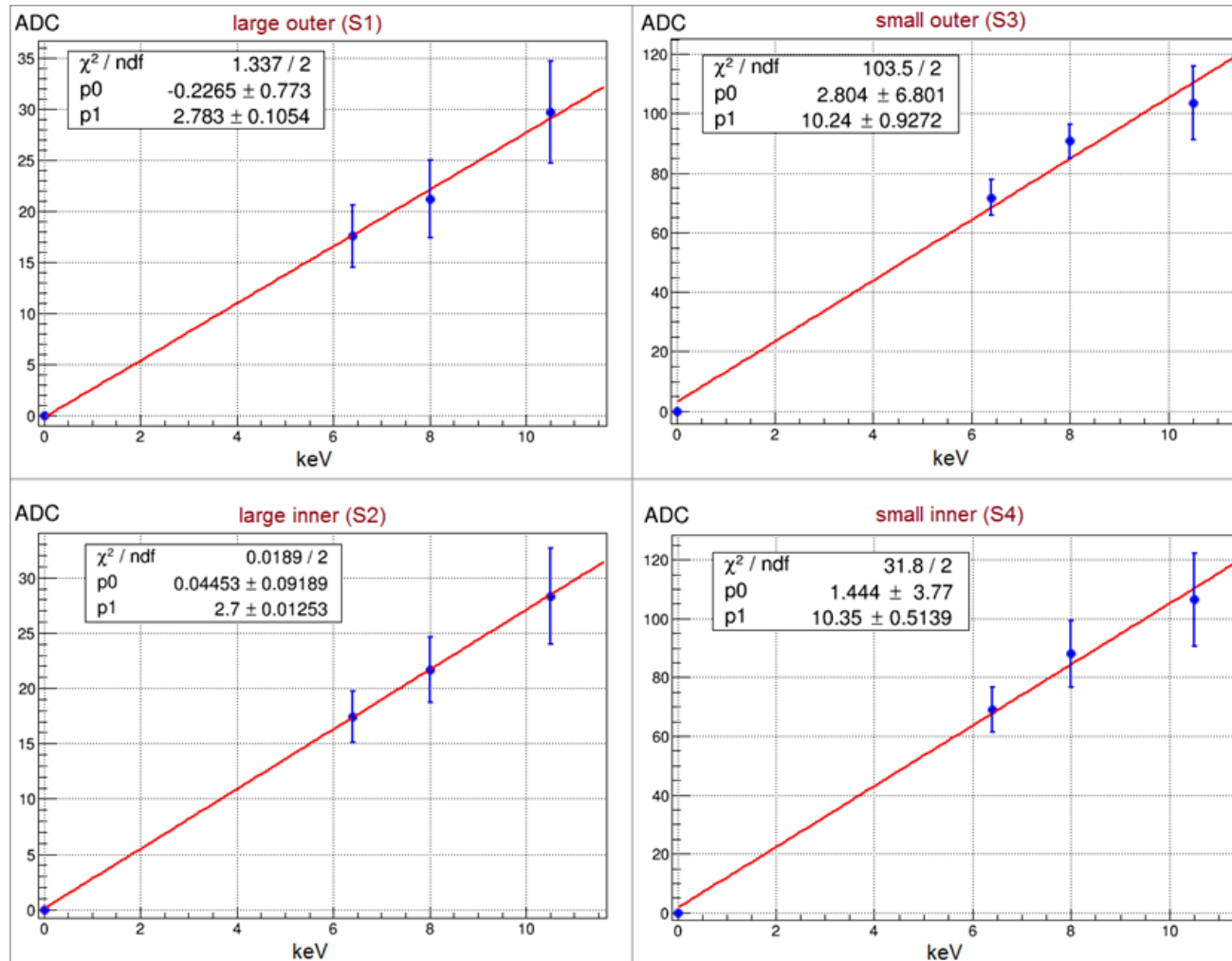
# Sensor Calibration

- ✓ X-ray photon energy  $\rightarrow$  ADC count – Tezzaron bonded chip



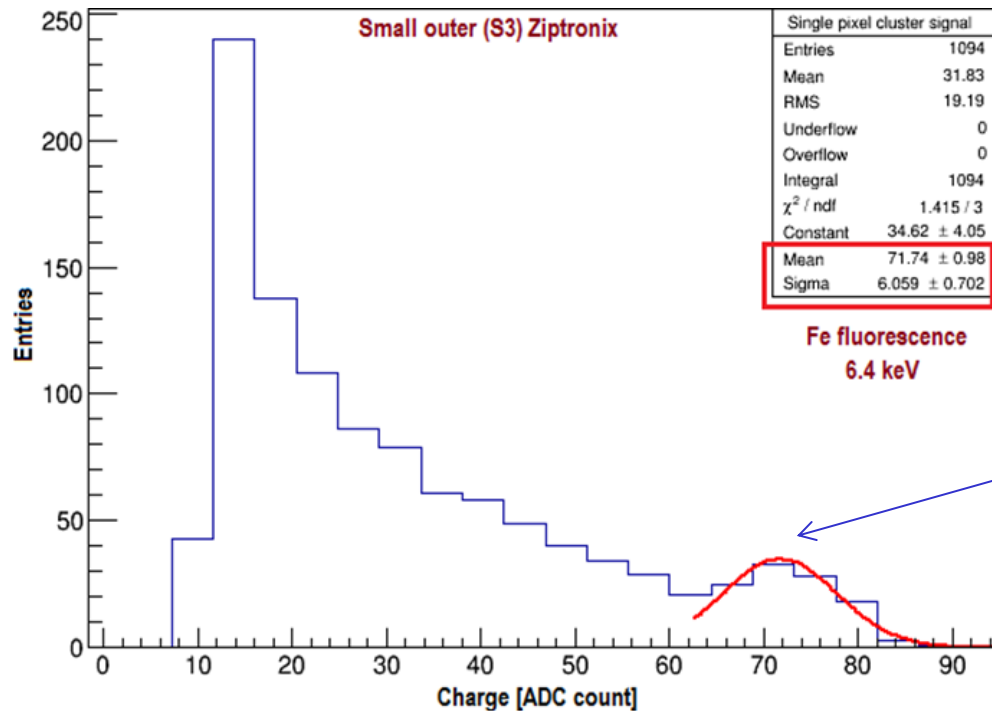
# Sensor Calibration (2)

- ✓ X-ray photon energy  $\rightarrow$  ADC count – Ziptronix bonded chip



# Sensor Calibration (3)

✓ Electrons -> ADC counts



Fe peak energy

$$e/h = \frac{6.4 \text{ keV}}{3.6 \text{ eV}} = 1777$$

Energy for e/h  
creation in Si

$$1777 / \text{Mean} = [e/\text{ADC}]$$

- ✓ 1 ADC count -> ~102e for the large photodiode pixel layout
- ✓ 1 ADC count -> ~25e for the **small** photodiode pixel layout

Better conversion gain

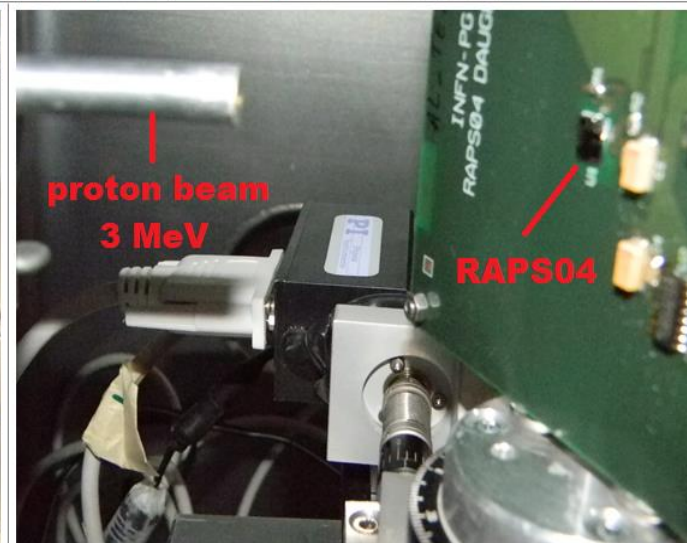
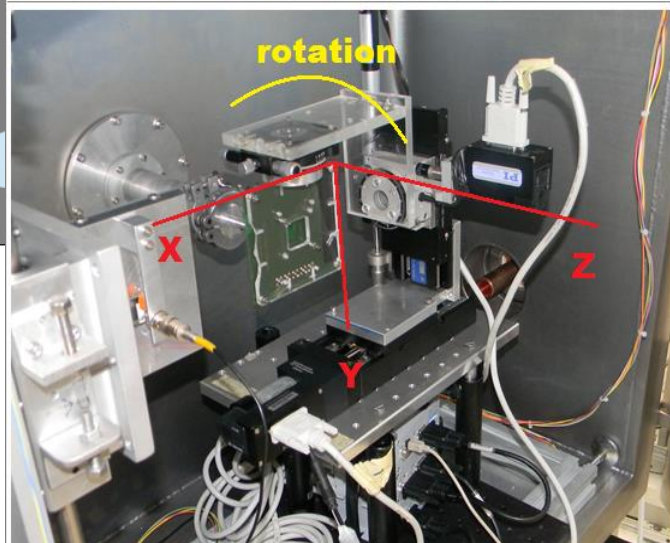
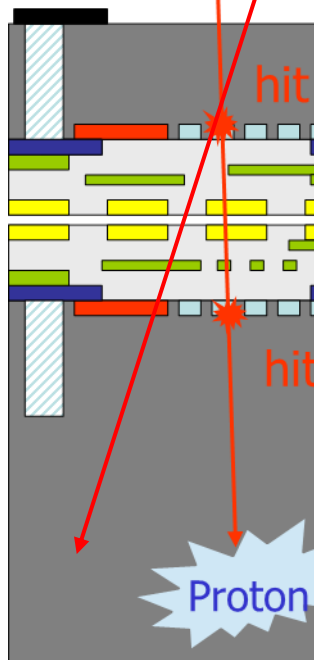
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# The set-up at LABEC (Florence, Italy)

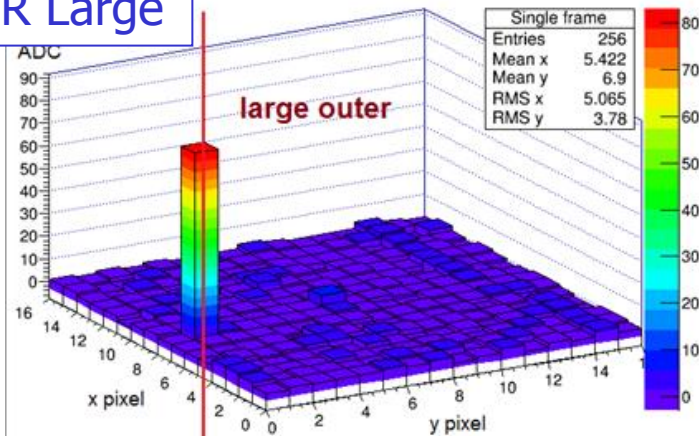
✓ 3MeV protons



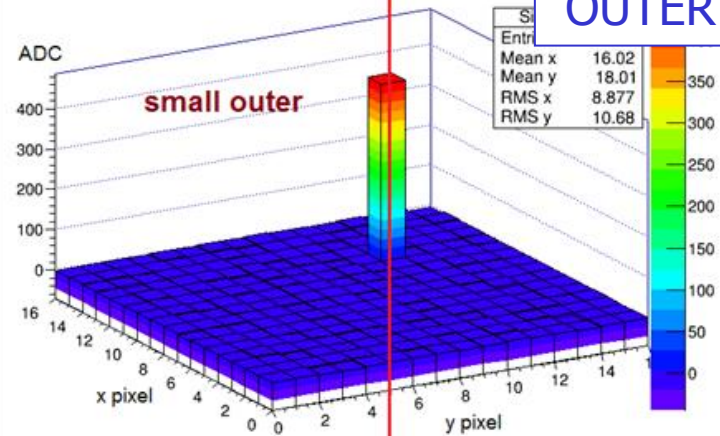
# 3 MeV protons response

✓ RAPS04-3D 3MeV protons – Outer & Inner tier coincidence responses

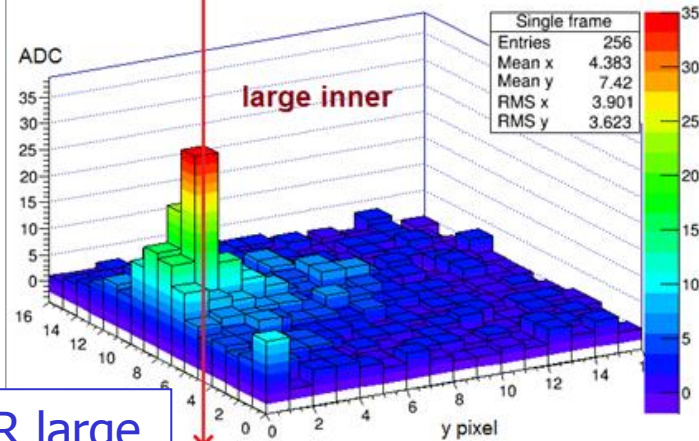
OUTER Large



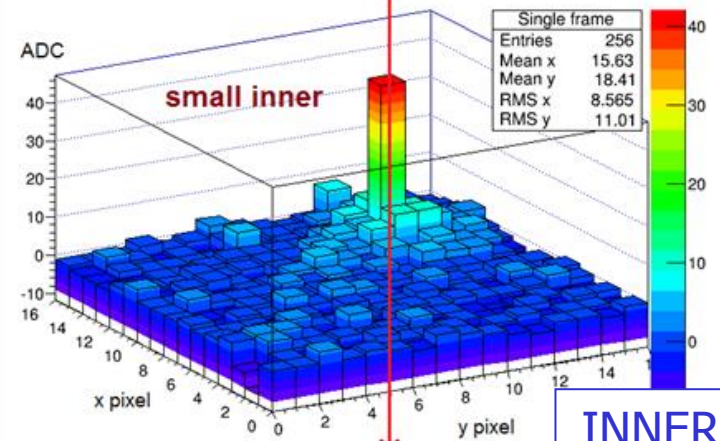
OUTER Small



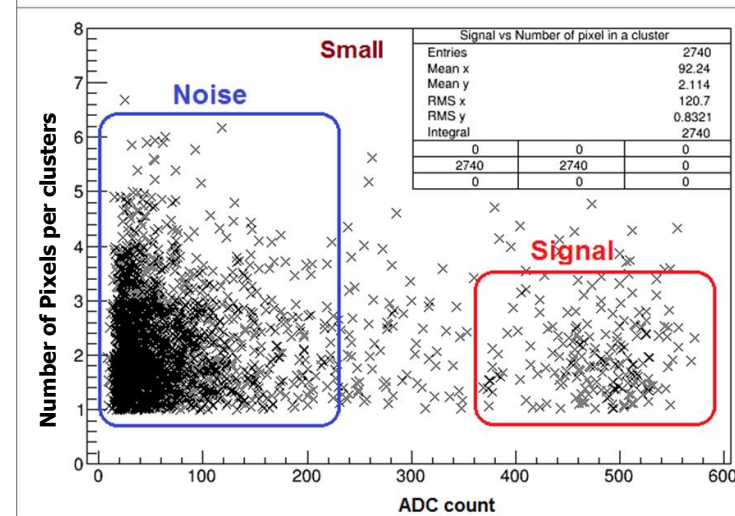
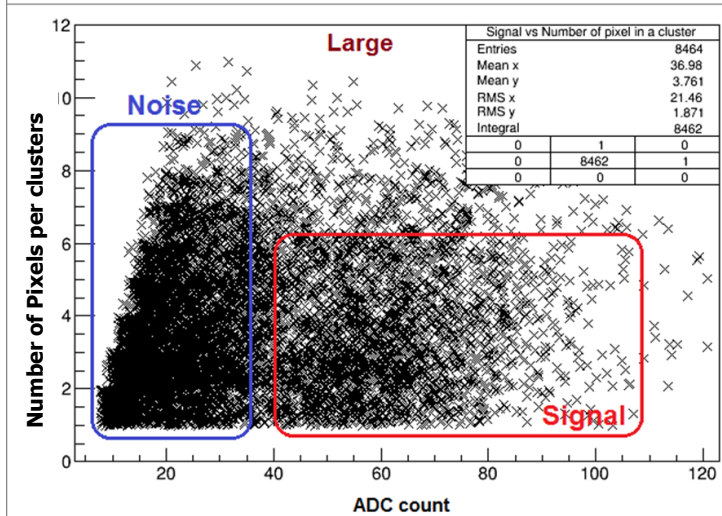
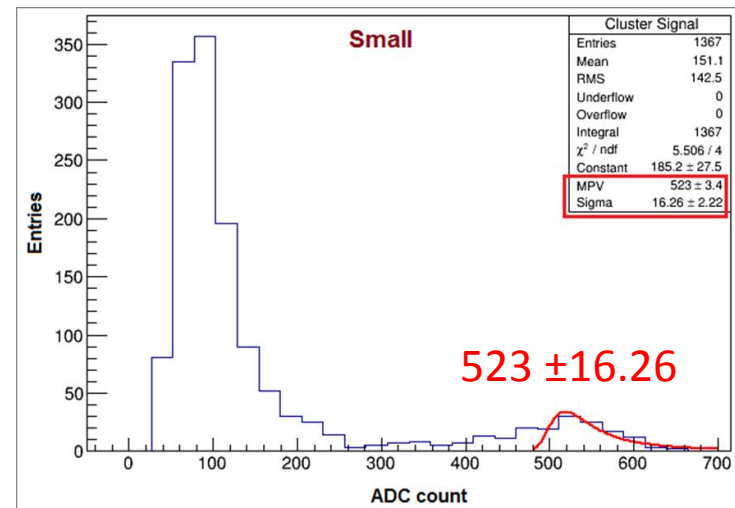
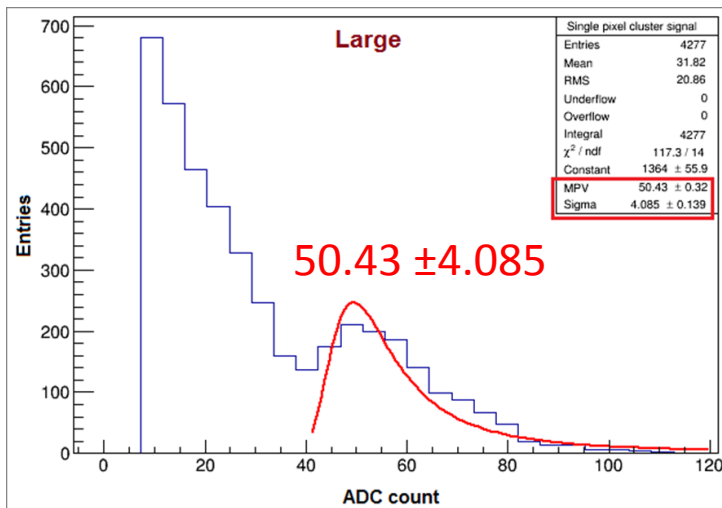
INNER large



INNER Small



# 3 MeV protons response (2)

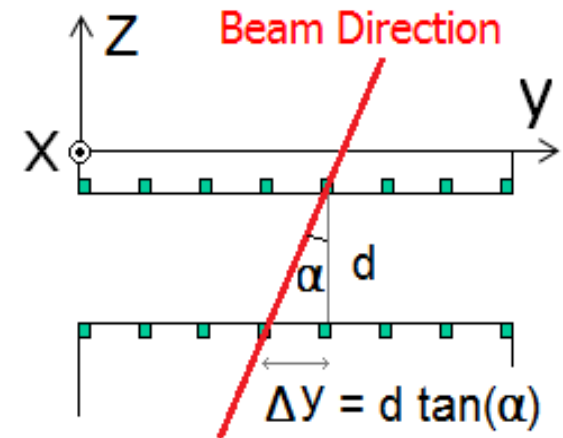
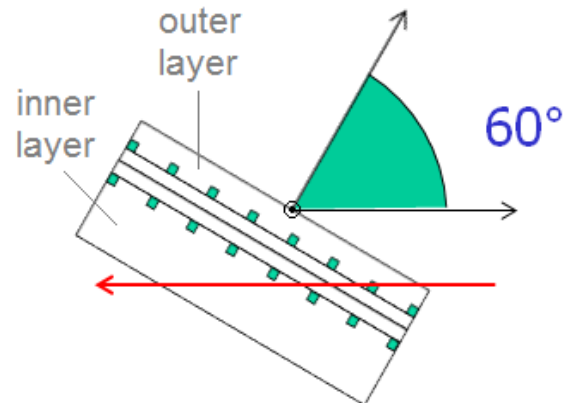
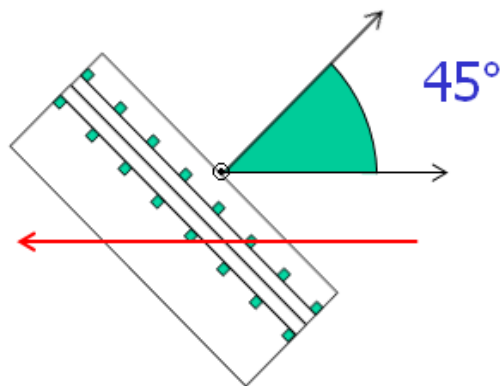
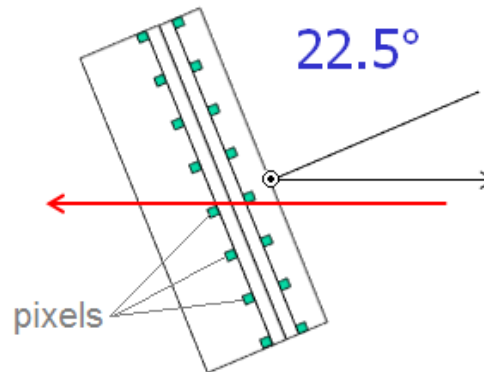
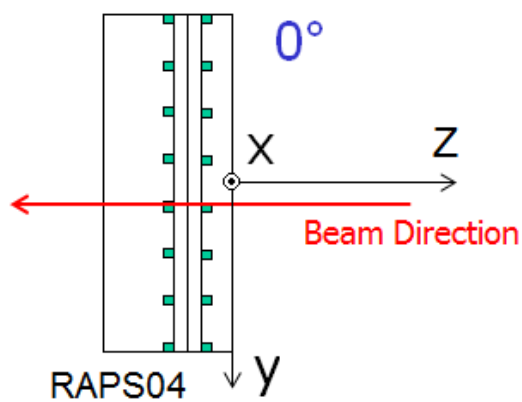


Signal distribution & Landau Fit (**LARGE**)

Signal distribution & Landau Fit (**SMALL**)



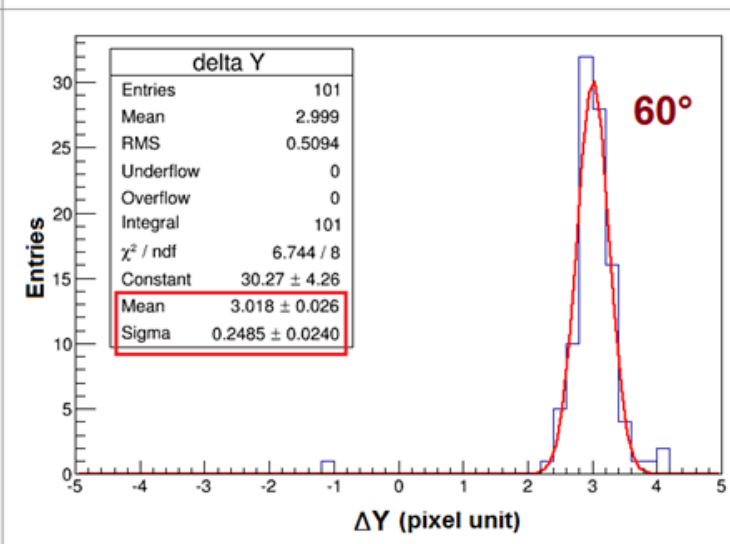
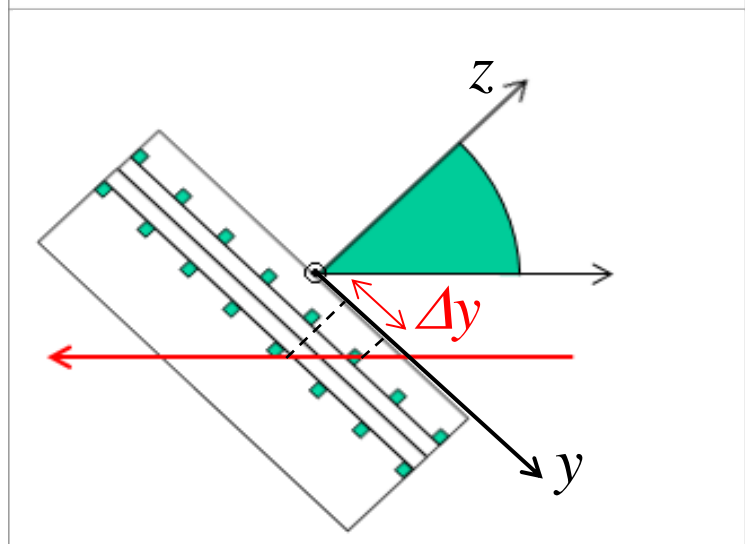
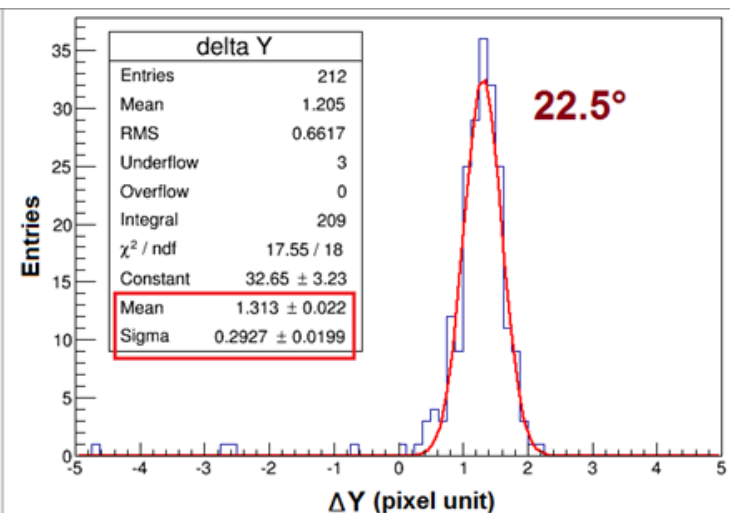
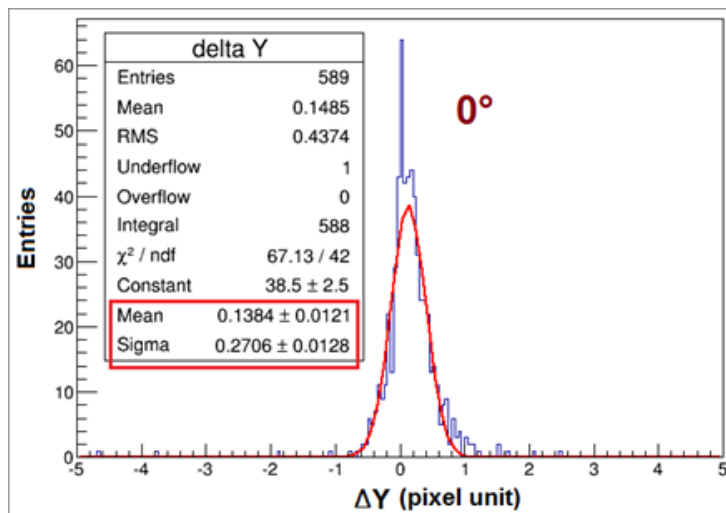
# Angular measurements



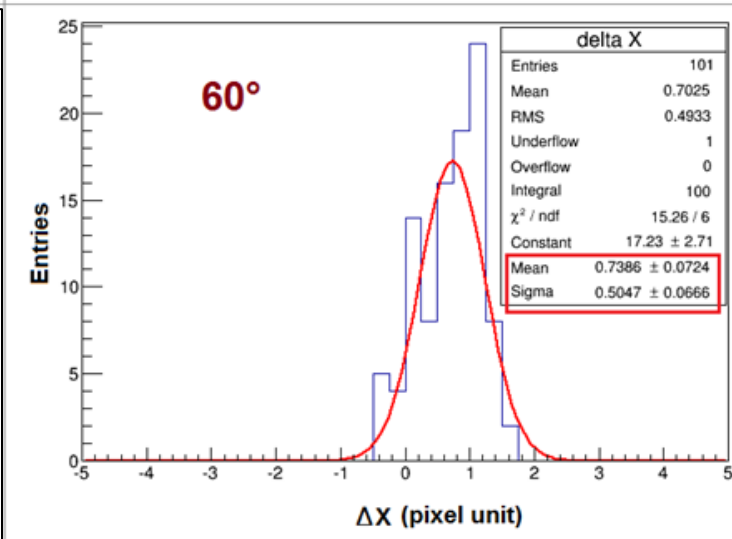
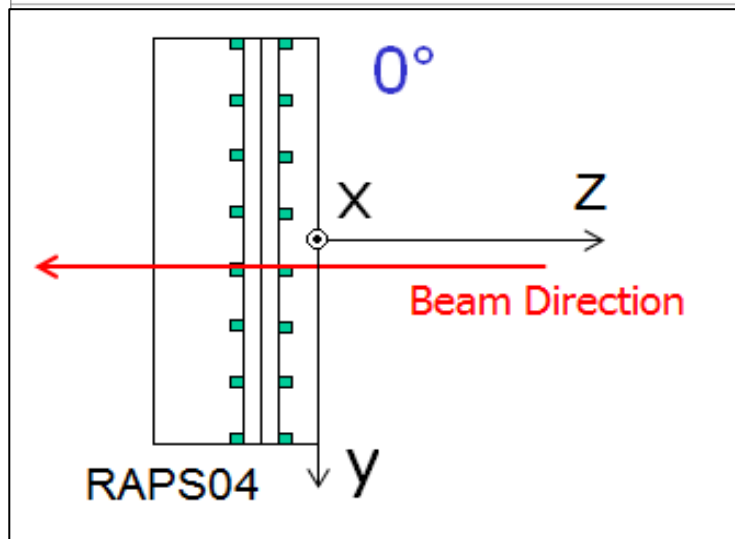
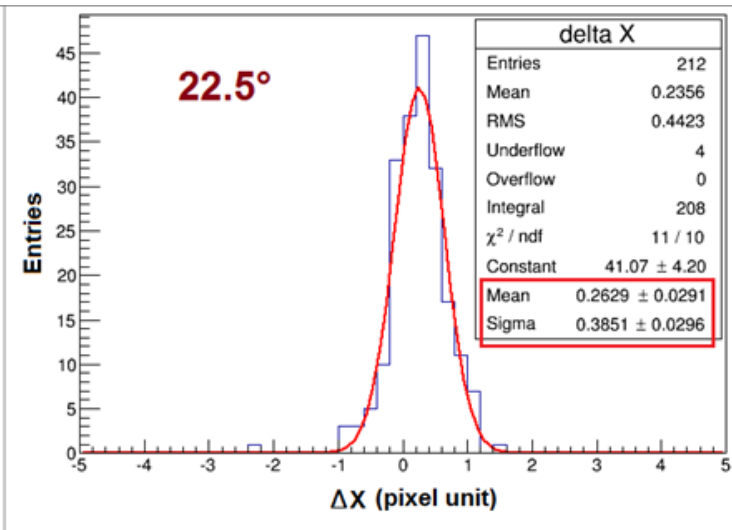
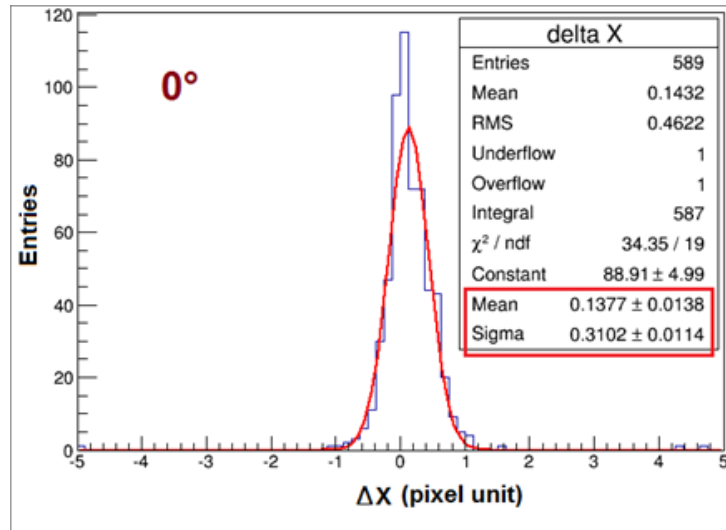
$$\alpha = \tan^{-1}\left(\frac{\Delta y}{d}\right)$$

- ✓ Residuals (outer – inner coordinates) for both directions.

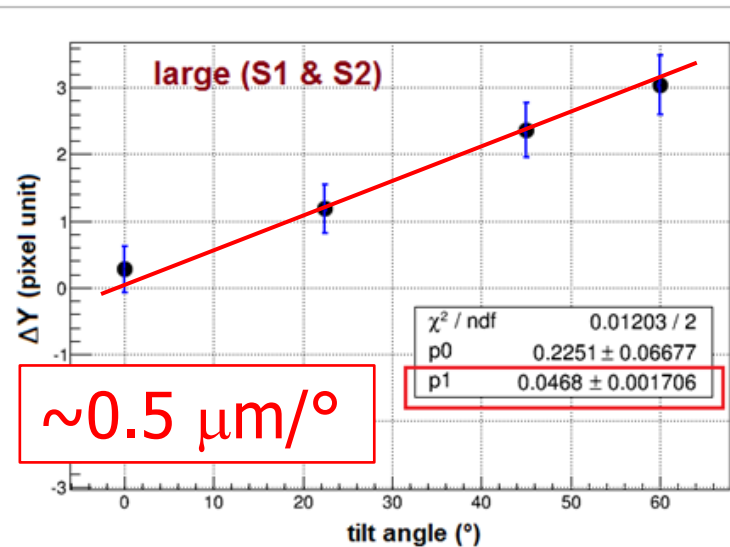
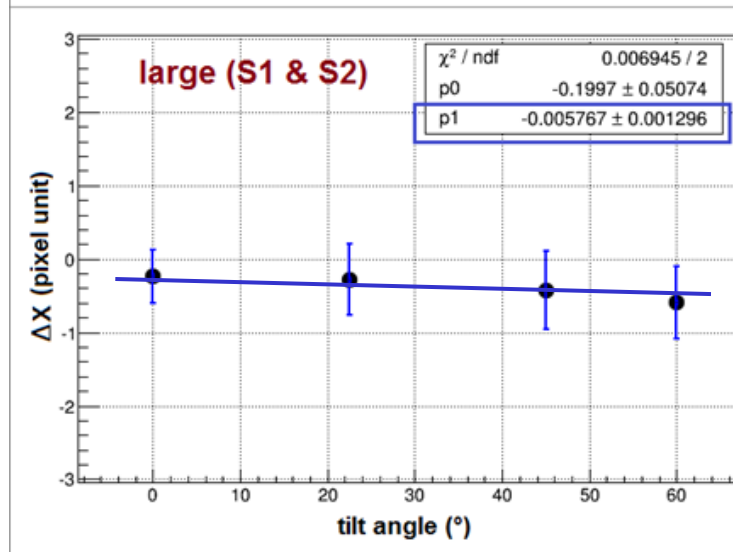
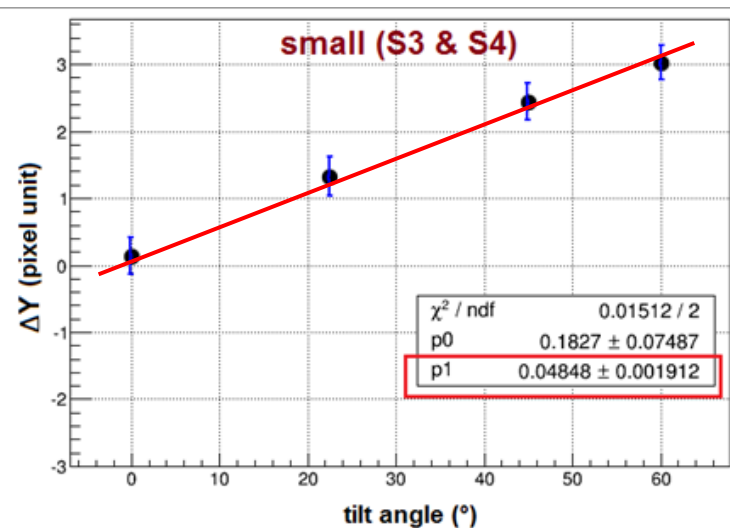
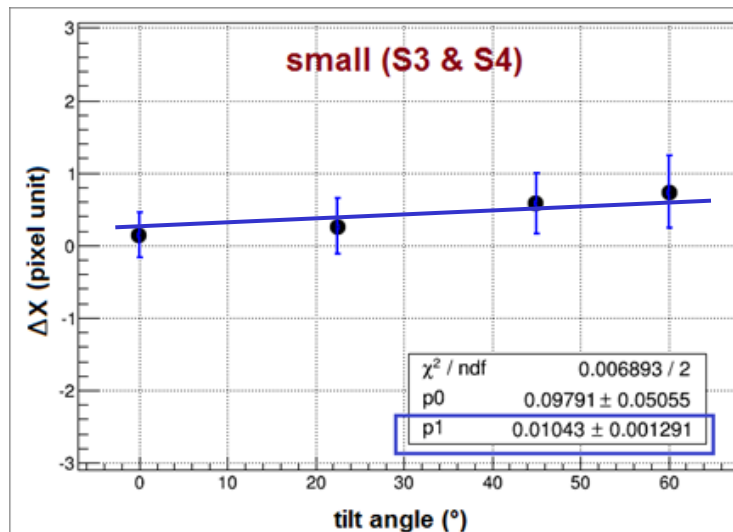
# Angular measurements: $y$ -axis displacement



# Angular measurements: $x$ -axis displacement



# Angular measurements: $\Delta x$ and $\Delta y$ vs. tilt angle



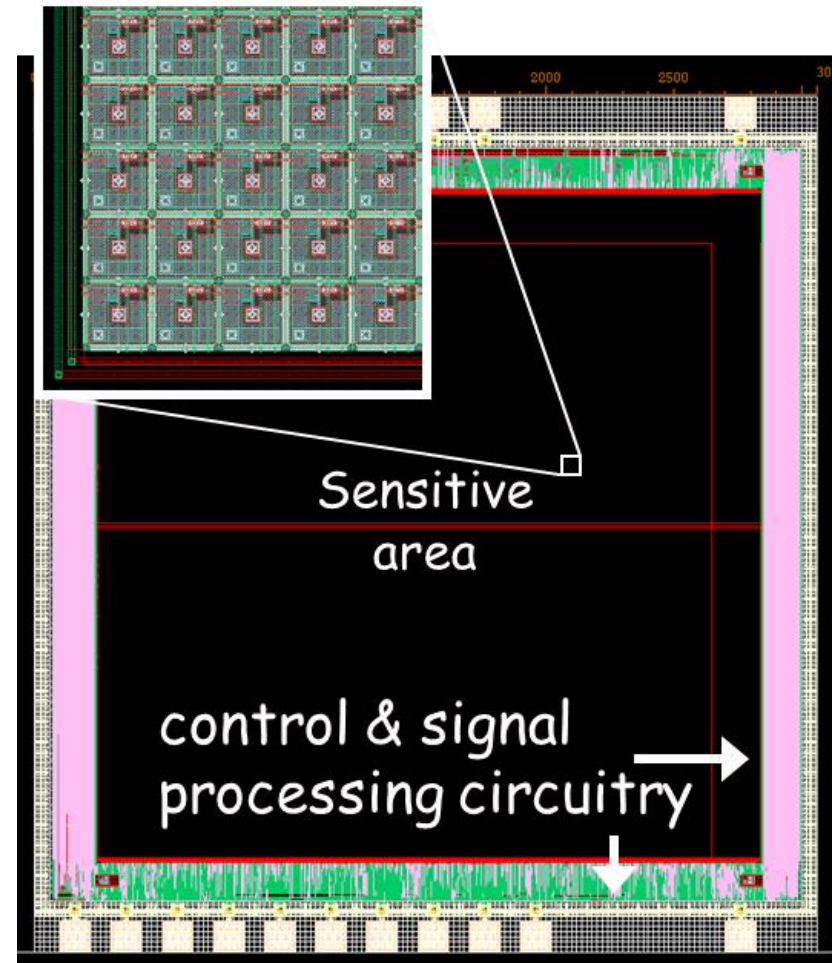
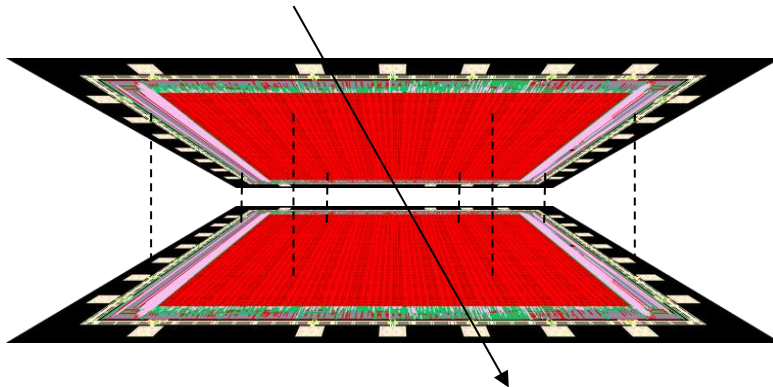
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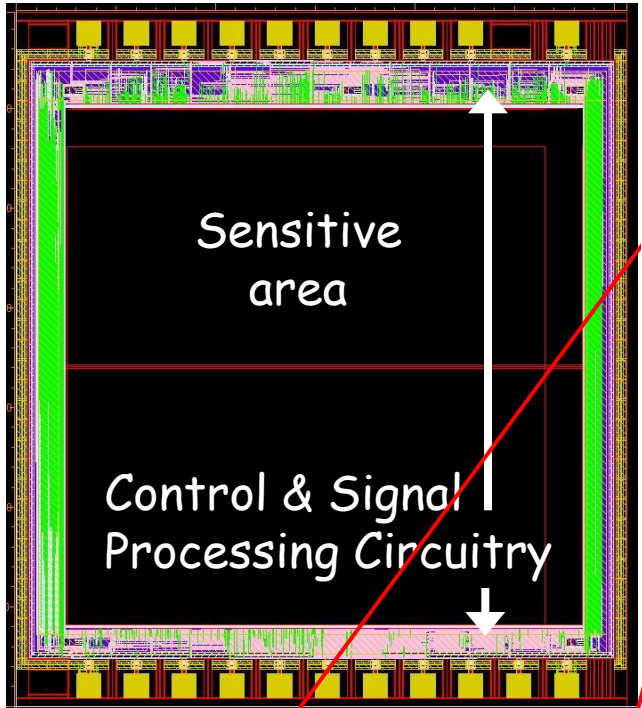
# RAPS05-3D

- ✓ New pixel design.
- ✓ Bigger matrix.
- ✓ 256x256 pixels ( $\sim 6.5\text{mm}^2$  area).
- ✓ APS - 3T pixel ( $10\mu\text{m} \times 10\mu\text{m}$ ).
- ✓ 4-parallel analog outputs.
- ✓ Control&signal processing circuitry: ARM (Artisan) SC library.

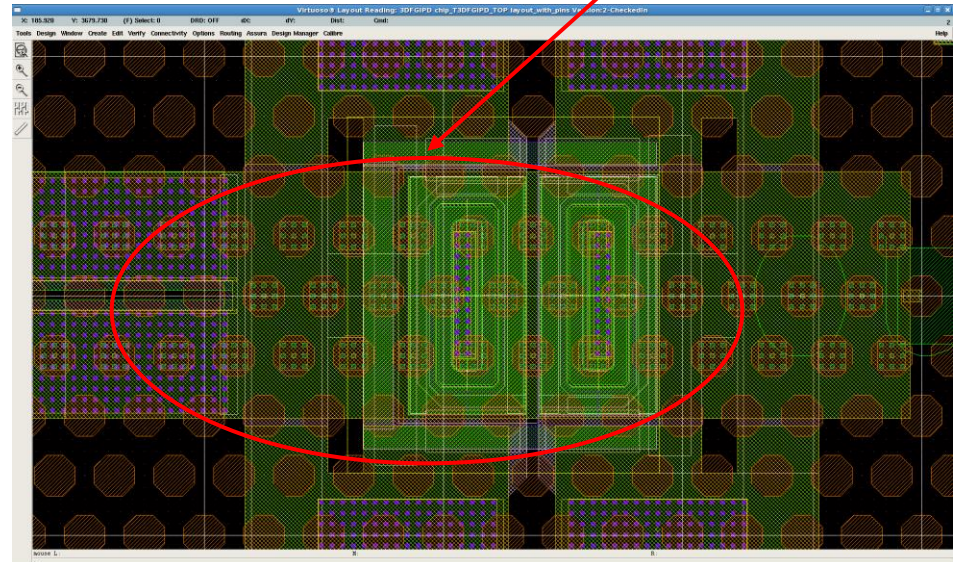
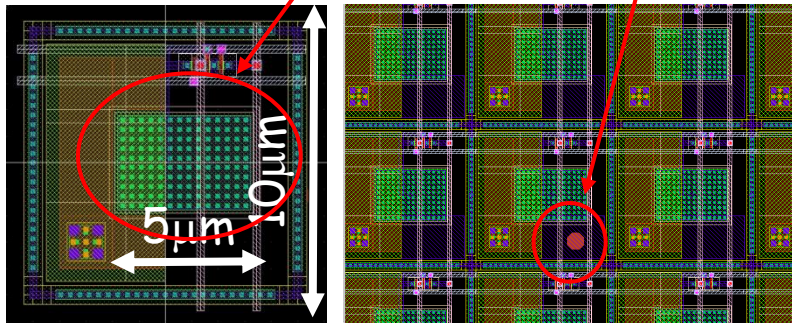


# RAPS05-3D (2)

← W = 3063um →

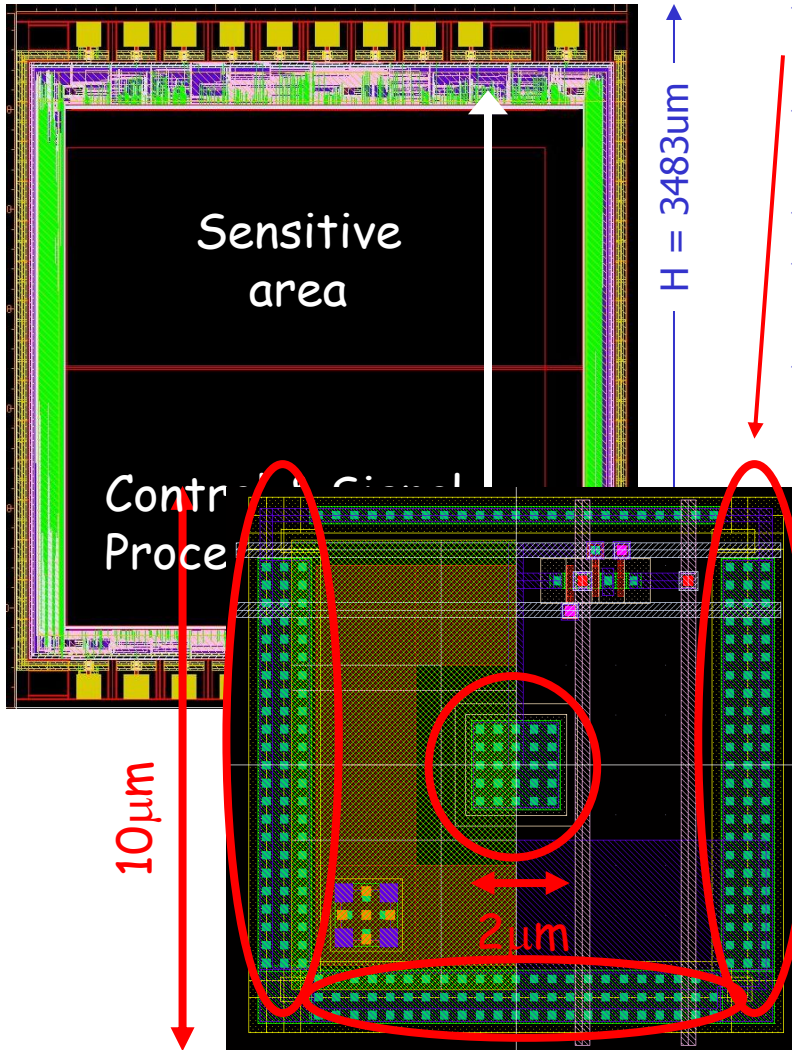


- ✓ COMP (local) density rules -> wider pixel sensitive area (n-well)
- ✓ Metal&Poly density -> non-uniform (local) metal dummy filling
- ✓ TSV density rules -> TSV dummies on array
- ✓ Contacts between tiers are located only at the chip periphery (e.g. within I/O PADs).
- ✓ Redundant bondpoint scheme has been adopted (as for RAPS04).

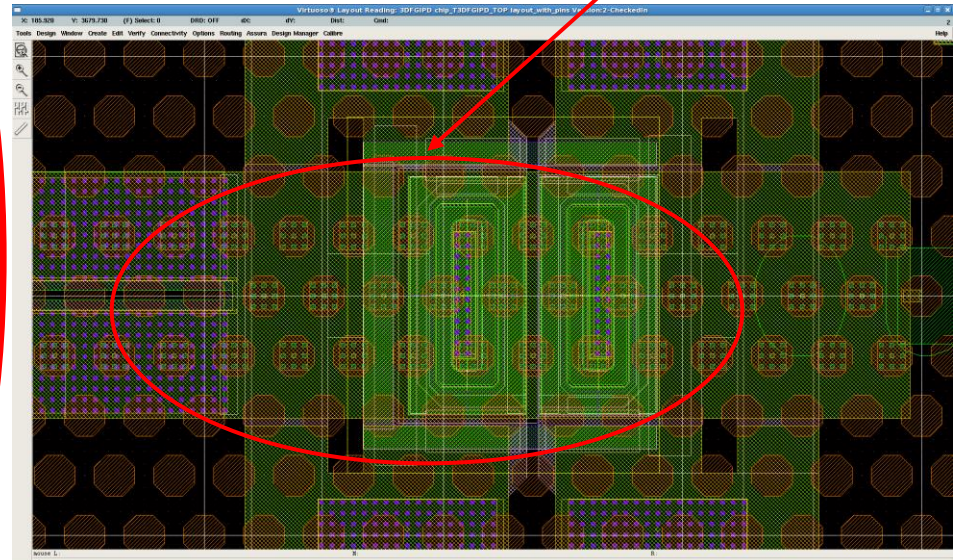


# RAPS05-3D (2)

← W = 3063 $\mu$ m →



- ✓ COMP (local) density rules -> different p-well guard layout & smallest n-well
- ✓ Metal&Poly density -> non-uniform (local) metal dummy filling
- ✓ TSV density rules -> TSV dummies on array
- ✓ Contacts between tiers are located only at the chip periphery (e.g. within I/O PADs).
- ✓ Redundant bondpoint scheme has been adopted (as for RAPS04).





# Conclusions

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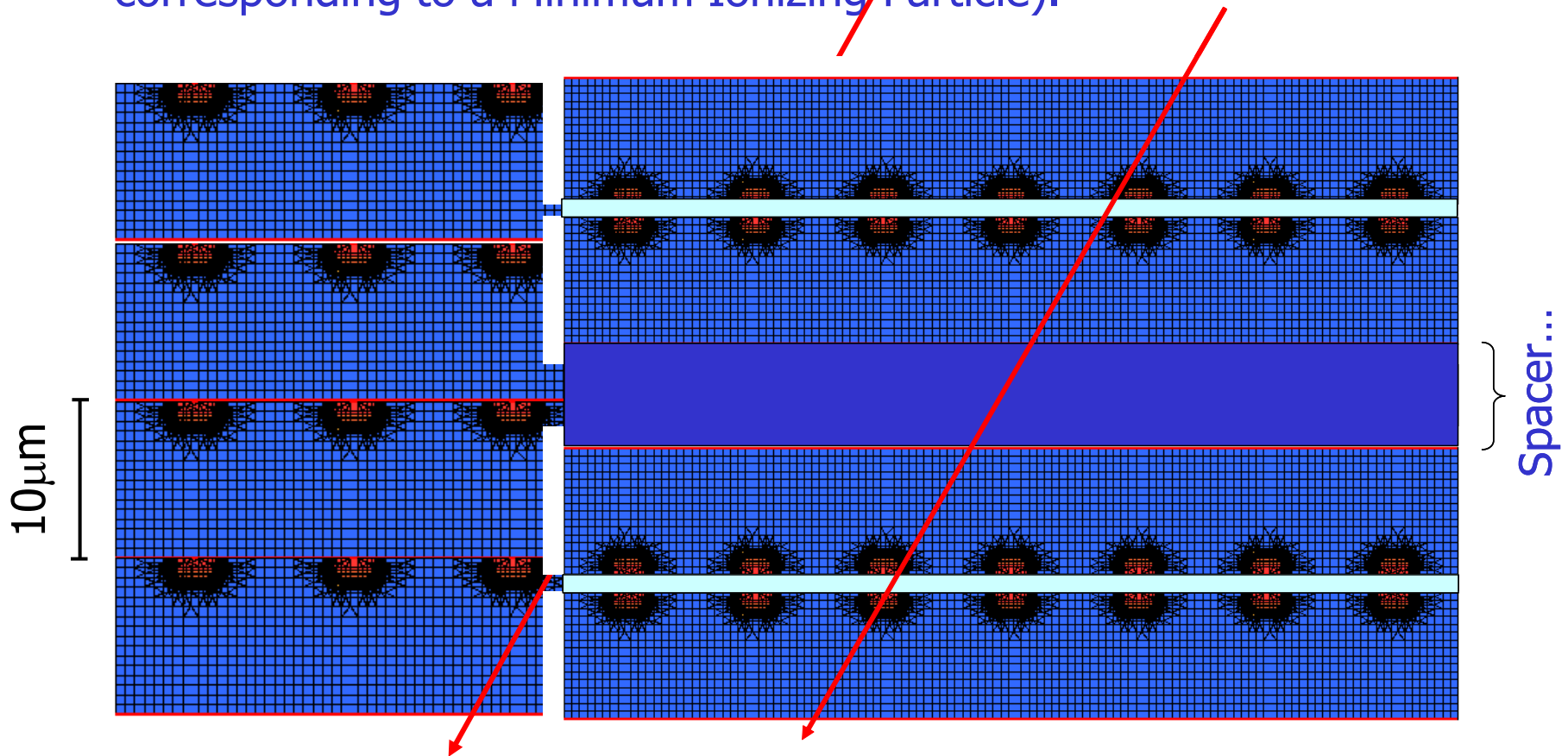
- ✓ Functional characterization of 3D monolithically stacked CMOS Active Pixel Sensors layers (beam test) fabricated in Chartered/Tezzaron 130nm 3D technology for particle tracking purposes.
- ✓ Coincidence responses between bottom and top matrices have been obtained with 3MeV protons from aligned tiers.
- ✓ Particle angular measurement can be carried out by parallel read-out of corresponding outer and inner pixel matrices.
- ✓ Momentum measurement with a single, multiple layers, 3D vertically stacked APS CMOS detector.
- ✓ Next prototype: bigger sensitive area (efficiency...) and optimized charge to voltage conversion gain (w.r.t. the technology node).

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# Backup Slides

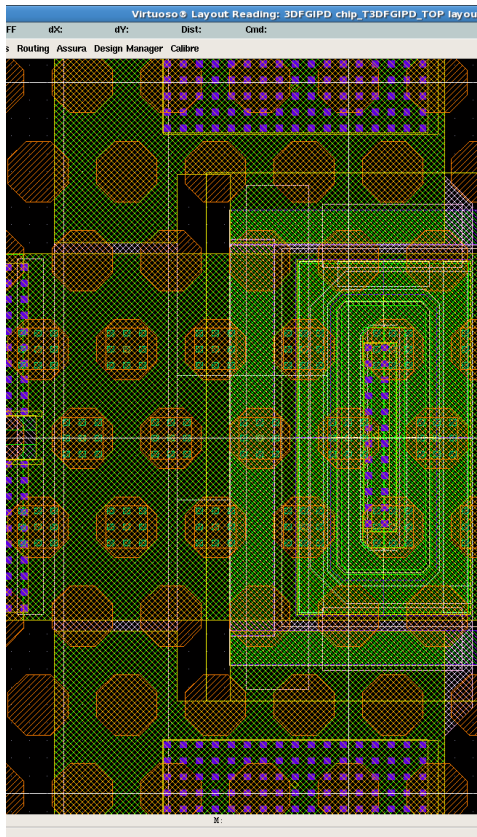
# 3D Monolithically Stacked CMOS APS

- ✓ Up to four (isolated) sub-arrays.
- ✓ Voltage response as a function of a particle hit (e/h pairs generation corresponding to a Minimum Ionizing Particle).

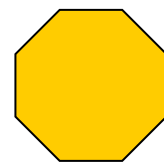
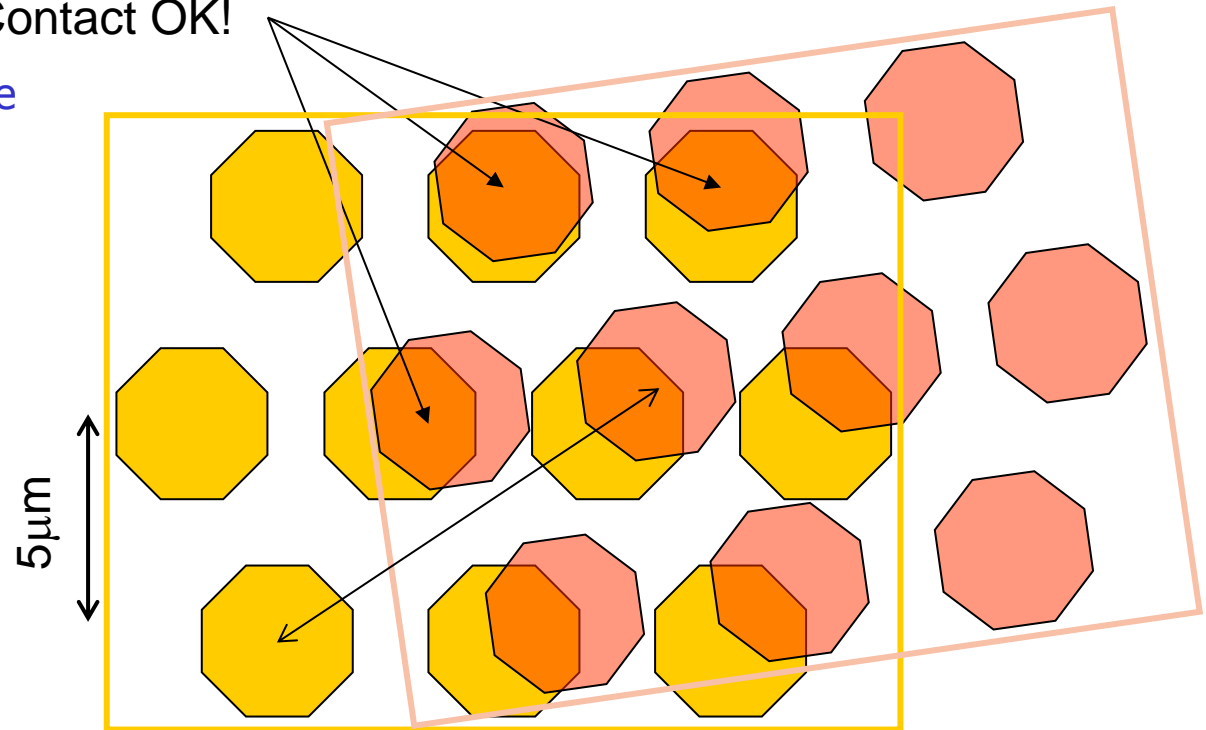


# The 3D Not Aligned is anyway ok...

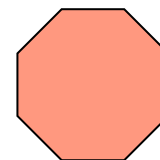
## Redundant bondpoint scheme



Contact OK!



bottom tier  
bondpoint



top tier  
bondpoint

# Top & Bottom tiers (mis)alignment!

- ✓ TOP/BOTTOM tier misalignment...
- ✓ RAPS04 3D tomography (courtesy of DESY - Hamburg)

